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AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application.

Claims 1-16. (Canceled)

Claim 17. (Canceled)

Claim 18. (Currently Amended) ~~The mask of claim 17~~ An alternating phase shifting mask for projecting an image on an image plane, the mask comprising:

a layout pattern having at least one element having a layout dimension, said layout dimension corresponding to a target image dimension in the image plane;

a phase shape having a phase width, wherein said phase shape is disposed adjacent to said layout dimension, and wherein said phase width is selected in accordance with a relationship between said phase width and said target image dimension wherein said relationship comprises across-chip line width variation (ACLV), and said phase width is selected so that ACLV is minimized.

Claim 19. (Currently Amended) ~~The mask of claim 17~~ An alternating phase shifting mask for projecting an image on an image plane, the mask comprising:

a layout pattern having at least one element having a layout dimension, said layout

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dimension corresponding to a target image dimension in the image plane;

a phase shape having a phase width, wherein said phase shape is disposed adjacent to said layout dimension, and wherein said phase width is selected in accordance with a relationship between said phase width and said target image dimension wherein said relationship comprises process window, and said phase width is selected so that said process window is maximized.

Claim 20. (Currently Amended) ~~The mask of claim 17~~ An alternating phase shifting mask for projecting an image on an image plane, the mask comprising:

a layout pattern having at least one element having a layout dimension, said layout dimension corresponding to a target image dimension in the image plane;

a phase shape having a phase width, wherein said phase shape is disposed adjacent to said layout dimension, and wherein said phase width is selected in accordance with a relationship between said phase width and said target image dimension wherein said phase width is about 0.8-1.2 times said layout dimension.

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